## P-3-12

# An Analysis of Layout and Temperature Effects on Magnetic-Coupling Factor, Resistive-Coupling Factor, and Power Gain Performances of RF Transformers for RFIC Applications

Yo-Sheng Lin, Chi-Chen Chen, Yan-Ru Tzeng, and Hsiao-Bin Liang

Department of Electrical Engineering, National Chi-Nan University, Puli, Taiwan, R.O.C. Phone: 886-4-92912198, Fax: 886-4-92917810, Email : stephenlin@ncnu.edu.tw

Abstract - In this paper, we demonstrate a comprehensive analysis of the temperature effect ( $-25 \,^{\circ}C \sim 175 \,^{\circ}C$ ) on the quality-factors (Q<sub>1</sub> and Q<sub>2</sub>), magnetic-coupling factor (K<sub>Im</sub>), resistive-coupling factor (K<sub>Re</sub>), maximum available power gain (G<sub>Amax</sub>), and minimum noise figure (NF<sub>min</sub>) performances of RF bifilar and stacked transformers for RFIC applications. Excellent G<sub>Amax</sub> of 0.713 and 0.806 (i.e. NF<sub>min</sub> of 1.469 dB and 0.937 dB) were achieved at 5 GHz and 7 GHz, respectively, at room temperature (RT), for a 1:1 stacked transformer mainly due to its high K<sub>Im</sub> and K<sub>Re</sub>. In addition, for the 1:1 bifilar transformer at RT, though its K<sub>Im</sub> and K<sub>Re</sub> are low, good G<sub>Amax</sub> of 0.636 and 0.631 (i.e. NF<sub>min</sub> of 1.965 dB and 2.0 dB) were still achieved at 5 GHz and 7 GHz, respectively, mainly due to its high Q<sub>1</sub> and Q<sub>2</sub>.

### I. Introduction

In the design of ultra-low-voltage high-performance transformer-feedback VCOs [1] and LNAs [2], the power gain G<sub>A</sub> (or noise figure NF) performance of the transformers used are crucial for the phase noise performance of the VCOs and the NF performance of the LNAs. However, the  $G_A$  (or NF) performance of monolithic RF transformers fabricated on normal silicon substrates are not satisfactory up to now mainly due to the K<sub>IM</sub>, the K<sub>Re</sub>, and the quality-factors (of the primary and the secondary coil) which are not high enough [3]. Various methods have been proposed to improve the Q-factors of RF passive devices, such as high-resistivity silicon, front-side and backside micromachining, porous silicon, proton implantation, and substrate transfer [3]. However, no detailed analyses of the layout and the temperature effects on the K<sub>Im</sub> and K<sub>Re</sub> performances of various important RF transformers have been reported. Therefore, in this work, we demonstrate an analysis of the temperature effect (-25 °C ~ 175°C) on the quality-factors (Q<sub>1</sub> and Q<sub>2</sub>),  $K_{Im}$ ,  $K_{Re}$ ,  $G_{Amax}$ , and  $NF_{min}$  performances of RF bifilar and stacked transformers for RFIC applications.

## **II. Transformer Structure**

The transformers under study were fabricated with a 0.18  $\mu$ m RF CMOS technology on a p-type silicon substrate (resistivity : 10  $\Omega$ -cm) with thickness of 700  $\mu$ m. The main features of the backend processes are as follows. There are 6 metal layers, named M1 to M6 from the bottom to the top. The thickness of M6 is 0.99  $\mu$ m, and that of M1-M5 is 0.53  $\mu$ m. Fig. 1 shows the 3D schematic diagrams of the 1:1 bifilar transformer (transformer-A), and the 1:1 stacked transformer (transformer-B). Table I is a summary of the primary layout parameters and the extracted small-signal equivalent circuit parameters of transformers A-E.

## **III. Measurement Results and Discussions**

The frequency-dependent S-parameter measurements were performed from 0.1 GHz to 20 GHz by an HP-8510C

network analyzer. Fig. 2(a) shows the measured equivalent Q-factors of the primary coil  $(Q_1)$  and the secondary coil  $(Q_2)$ of transformer-A and transformer-B. Good Q1 of 8.8 and 9.4, Q<sub>2</sub> of 7.5 and 7.1 were achieved at 5 GHz and 7 GHz, respectively, for transformer-A. This is better than that (i.e.  $Q_1$  of 5.8 and 1.6,  $Q_2$  of 3.6 and 1.6 at 5 GHz and 7 GHz, respectively) of the transformer-B. The higher Q1 and Q2, and the larger self-resonance frequency of the primary coil (f<sub>SR1</sub>) and the secondary coil (f<sub>SR2</sub>) of transformer-A are attributed to its lower series metal resistances R<sub>s1</sub> and R<sub>s2</sub>, and lower parasitic (or overlap) capacitance C<sub>p</sub> between the primary coil and the secondary coil (see Table I). Fig. 2(b) shows the measured K<sub>IM</sub> and K<sub>Re</sub> of transformer-A and transformer-B. As can be seen, high  $K_{Im}$  of 1.083 and 1.009,  $K_{Re}$  of 0.487 and 0.977 were achieved at 5 GHz and 7 GHz, respectively, for transformer-B. This is better than that (i.e.  $K_{Im}$  of 0.536 and 0.522,  $K_{Re}$  of 0.111 and 0.15 at 5 GHz and 7 GHz, respectively) of transformer-A. The higher  $K_{Im}$  and  $K_{Re}$  of transformer-B is attributed to its smaller equivalent vertical distance (VD) [4].

Fig. 3(a) shows the measured  $Q_1$ and  $O_2$ of transformer-A at various temperatures. As can be seen, the measured  $Q_1$  and  $Q_2$  decrease with the increase of temperature mainly due to the positive temperature coefficient of the series metal resistance R<sub>s1</sub> and R<sub>s2</sub>. The measured temperature dependence of R<sub>1-eff</sub> at low frequencies (i.e. R<sub>s1</sub>) is linear. The corresponding temperature coefficient is  $3.94 \times 10^{-3}$  C at 0.1 GHz, which is very close to the result  $(3.9 \times 10^{-3})^{\circ}$ C) reported in the literature. Fig. 3(b) shows the measured K<sub>IM</sub> and K<sub>Re</sub> of transformer-A at various temperatures. As can be seen, the temperature dependences of both  $K_{IM}$  and  $K_{Re}$  are very weak. Fig. 6(c) shows the measured GAmax both before and after the test pads were de-embedded of transformer-A at various temperatures. Fig. 7(a) shows the measured  $Q_1$  and  $Q_2$  of transformer-B at various temperatures. Fig. 7(b) shows the measured  $K_{IM}$  and  $K_{Re}$  of transformer-B at various temperatures. Fig. 7(c) shows the measured G<sub>Amax</sub> of transformer-B at various temperatures both before and after the test pads were de-embedded. The same trends as those of transformer-A were observed.

### **IV. Conclusions**

The present analysis is helpful for RF engineers to design temperature-insensitive ultra-low-voltage high-performance transformer-feedback RF-ICs.

#### Reference

- K. Kwok, and H. C. Luong, *IEEE Journal of Solid-State Circuits*, vol. 40, no. 3, pp. 652-660, Mar. 2005.
- [2] D. J. Cassan, and J. R. Long, *IEEE Journal of Solid-State Circuits*, vol. 38, pp. 427-435, Mar. 2003.
- [3] K. T. Ng, B. Rejaei, and J. N. Burghartz, *IEEE Trans. on Microwave Theory and Techniques* vol. 50, no. 1, pp. 377-383, Jan. 2002.
- [4] H. M. Hsu, *IEEE Trans. on Electron Devices*, vol. 52, no. 7, pp. 1410-1414, Jul. 2005.

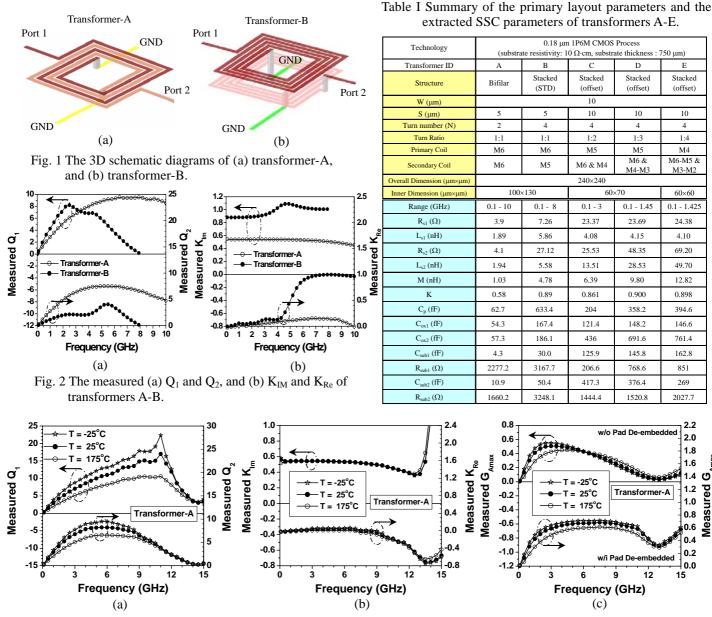


Fig. 3 The measured (a) Q<sub>1</sub> and Q<sub>2</sub>, (b) K<sub>IM</sub> and K<sub>Re</sub>, and (c) G<sub>Amax</sub> (both before and after the test pads were de-embedded) of transformer-A at various temperatures (-25°C, 25°C, and 175°C).

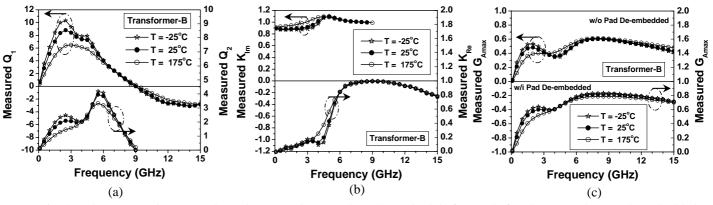


Fig. 4 The measured (a)  $Q_1$  and  $Q_2$ , (b)  $K_{IM}$  and  $K_{Re}$ , and (c)  $G_{Amax}$  (both before and after the test pads were de-embedded) of transformer-B at various temperatures (-25°C, 25°C, and 175°C).